

A Wideband 60 GHz Class-E/F₂ Power Amplifier in 40nm CMOS

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Abstract— This paper presents a fully integrated 60 GHz power amplifier in 40 nm CMOS that reaches the highest reported product of power-added efficiency and bandwidth. It is achieved through low/moderate coupling-factor transformers in the preliminary stages and a proper second harmonic termination of the output stage, such that it can operate as a class-E/F₂ switched-mode PA at the saturation point. The three-stage PA delivers 17.9 dBm saturated output power with 20% peak PAE. It demonstrates a bandwidth of 9.7 GHz with a peak gain of 21.6 dB.

Index Terms— Power amplifier, mm-wave, class-E/F₂, switched-mode, transformer, PA stability

I. INTRODUCTION

A key challenge of 60 GHz CMOS radios is a poor efficiency of their power amplifier (PA). Employing nonlinear switched-mode PAs within digitally intensive transmitter architectures, such as outphasing and direct digital-to-RF conversion [1], can improve the total system efficiency. However, switching at mm-wave is not trivial due to the large output capacitance and low current driving capability of CMOS transistors.

In this paper we propose a new architecture of a fully integrated *switched-mode* wideband 60 GHz PA in standard digital 40 nm CMOS. By a proper second-harmonic termination of its output matching network, the required systematic peak current of the final stage is reduced such that it can act as a class-E/F₂ *switched-mode* PA at saturation. Transformers of low/moderate coupling are also utilized in the preliminary stages to improve the overall bandwidth. We also propose a technique to stabilize transformer-based mm-wave amplifiers against various modes of undesired oscillations.

II. BENEFITS AND CONSTRAINTS OF CLASS-E/F PA

It is shown in Kee et al. [2] that drain efficiency η_D of zero-voltage switching (ZVS) PA of Fig. 1 (a) can be written in terms of a set of technology dependent parameters (R_{on} , C_{out}) and a set of matching network or waveform dependent parameters (F_C , F_{PI} , F_I). To better understand the tradeoffs in mm-wave designs, we extend the results of [2] to:

$$\eta_D = 1 - \frac{R_{on} I_{rms}^2}{V_{DD} I_{DC}} = 1 - \left(\frac{I_{rms}}{I_{DC}} \right)^2 \frac{I_{DC}}{C_S \omega_0 (V_{DD} - V_{sat})} \cdot \left(\frac{V_{DD} - V_{sat}}{V_{DD}} \right) \left(\frac{C_S}{C_{out}} \right) (R_{on} C_{out}) \omega_0. \quad (1)$$

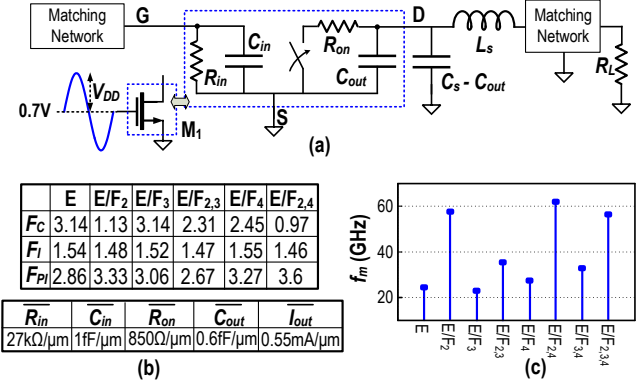


Fig. 1. (a) Class-E/F PA schematic; (b) waveform FoM and technology parameters; (c) maximum operating frequency for different flavors of class-E/F PA in TSMC 40 nm LP CMOS, as predicted from (6).

The waveform FoM's are defined as

$$F_I = \frac{I_{rms}}{I_{DC}}, F_C = \frac{I_{DC}}{C_S \omega_0 (V_{DD} - V_{sat})}, F_{PI} = \frac{I_{peak}}{I_{DC}}. \quad (2)$$

where R_{on} and C_{out} are, respectively, on-state channel resistance and off-state output capacitance of M_1 transistor. Note that $R_{on} \times C_{out}$ is invariant to changes of M_1 's width. I_{DC} and I_{rms} are defined as the average and RMS values of M_1 drain current, and C_S is the PA desired shunt capacitance to satisfy the ZVS criterion. V_{sat} represents the transistor's average V_{DS} in on-state. Note that since F_C should not change over the $\omega_0 = 2\pi f_0$ operating frequency, C_S has to reduce with increasing f_0 . Hence, C_S limits the transistor's width at mm-wave, which leads to a dramatic increase in R_{on} and thus V_{sat} of the switching device. Consequently, we include the effect of V_{sat} in η_D and F_C definitions in (1) and (2) to achieve more practical analytic results than in [2]. V_{sat} can be calculated from

$$P_{Loss} = V_{sat} I_{DC} = R_{on} I_{rms}^2 \rightarrow V_{sat} = R_{on} I_{DC} F_I^2. \quad (3)$$

By replacing $I_{DC} = F_C C_S \omega_0 (V_{DD} - V_{sat})$ in (3),

$$V_{sat} = V_{DD} \frac{F_C F_I^2 R_{on} C_{out} \omega_0}{\alpha + F_C F_I^2 R_{on} C_{out} \omega_0} \quad (4)$$

where $\alpha = C_{out}/C_S$ denotes how much the required C_S for the class-E/F operation is occupied by M_1 's self-capacitance. It is also instructive to go one step further than [2] and calculate the class-E/F PA characteristics

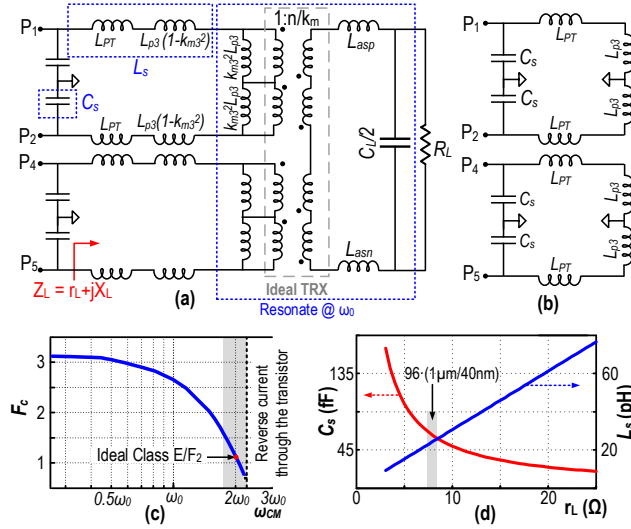


Fig. 3. Equivalent half-circuit model of output matching network for (a) DM, and (b) CM excitations; (c) F_c versus CM resonant frequency; (d) required L_s and C_s for class-E/F operation versus resistive load seen by switch transistor.

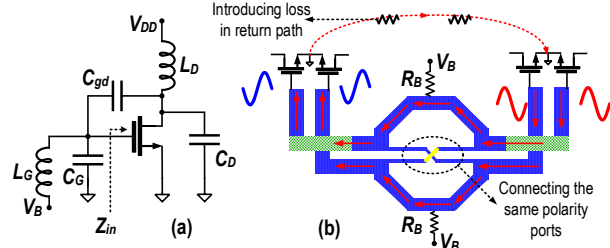


Fig. 4. (a) Half-circuit of PA pseudo-differential stage, (b) damping the undesired combination of CM and DM oscillation.

Figure 3(d) shows the optimum required class-E/F₂ PA shunt capacitance C_s and series inductance L_s at fundamental frequency versus the load resistance presented by the matching network. The matching network geometry design is initiated by choosing the switch transistor dimension such that its output capacitor absorbs the entire C_s . However, C_s also depends on L_s and the load resistance presented by the matching network, as can be gathered from Fig. 3(d). Hence, several iterations are needed to find the optimal size combination of the transistor, transformer and matching network. This procedure results in an optimal unit power transistor size of 96 (1 μ m/40nm) with 1.3 dB insertion loss of the output matching network. Note that the class-E/F₂ optimal combination is different from the goal of maximizing the output power or gain.

Each pseudo-differential pair along with their parasitic capacitance C_{gd} and matching networks (see Fig. 4(a)) can potentially act as two coupled Pierce oscillators and create CM instability. It can be shown that its resonant frequency is very close to the operating frequency (≈ 0.7 – $0.8\omega_0$) such

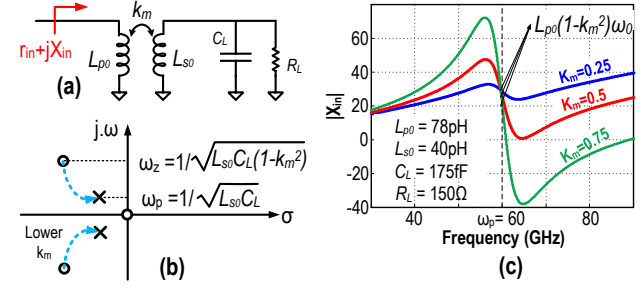


Fig. 5. (a) Transformer for inter-stage matching, (b) poles and zeros of X_{in} , (c) $|X_{in}|$ versus frequency for different k_m .

that neither adding an RC stabilization network at the MOS gate nor matching network loss can dampen the oscillation without affecting the precious power gain at ω_0 . Fortunately, using relatively large resistors ($R_B \sim 3$ k Ω) between the center tap of the secondary windings of the input and inter-stage transformers and gate bias voltage can cancel out the CM currents at the transformer secondary winding. Hence, any CM oscillation will be dampened. Nevertheless, a combination of CM and differential-mode (DM) oscillation can potentially happen in the transformer splitter. As shown in Fig. 4(b), each differential pair could oscillate in CM but with 180° phase shift to each other. Hence, neither neutralization capacitors nor R_B will damp this oscillation. We propose adding a weak cross connection between the splitter's in-phase ports to reduce the loop gain in this oscillation mode without affecting the splitter's main function. Another solution would be to add a lossy path between the ground connections of two pseudo-differential pairs across the splitter.

The effective Q-factor of the PA input/output matching network is degraded by the 50 Ω load and RF pad parasitic capacitance, $C_L \leq 50$ fF, to about 1–2 at 60 GHz, thus making these networks wideband. However, the input impedance of MOS transistors is considered as load to the inter-stage matching network, where $Q_{eff} = \overline{R_{in} C_{in} \omega_0} \approx 10$ at 60 GHz. Hence, the impedance seen at the input of the transformer network ($r_{in} + jX_{in}$ in Fig. 5(a)) changes significantly over frequency and thus limits the PA BW. Figure 5(b) depicts the position of zeros and poles of the X_{in} transfer function. Under a high k_m case (≥ 0.7), the conjugate zeros pair occurs at much higher frequency than the poles of the system. Hence, a large variation is seen in X_{in} (see Fig. 5(c)). However, the zero/pole pairs come closer together with lower k_m and a flatter region is observed in the X_{in} plot. Hence, the transistor sees its desired impedance over a wider frequency range. The additional insertion loss penalty is only ≤ 1.5 dB over the BW by using a $k_m = 0.25$ transformer. That penalty happens at the primary stages where it has negligible effect on the total PAE [4].

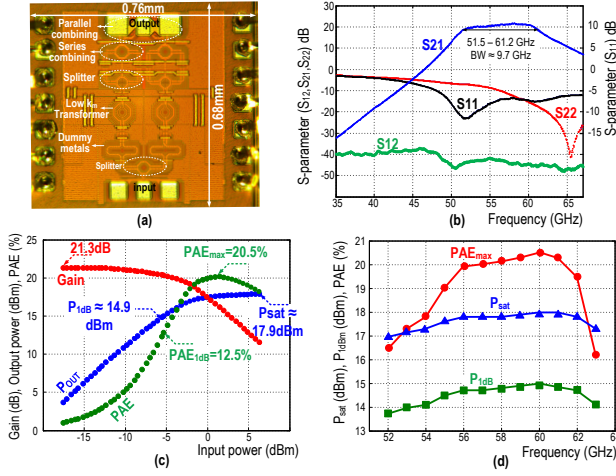


Fig. 6. (a) Chip micrograph; (b) measured S-parameters; (c) large-signal measurement at 60 GHz; (d) PA characteristics versus frequency.

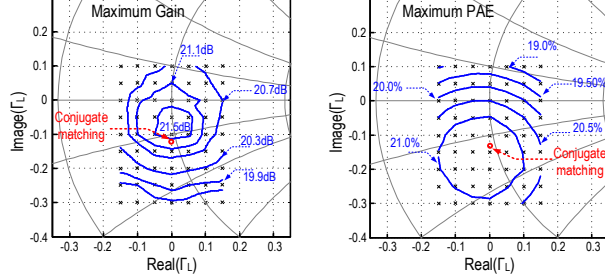


Fig. 7. Measured constant maximum gain and PAE contours.

TABLE I
COMPARISON TABLE OF 60 GHz CMOS POWER AMPLIFIERS

	This work	[6]	[1]	[3]	[4]
Technology	40nm LP	40nm LP	65nm GP	65nm GP	28nm LP
V _{DD}	1V	1V	1V	1V	2.1V
Gain(dB)	21.5	17	N/A	20.3	24.4
BW _{-3dB}	9.7GHz	5.5GHz	7GHz	9GHz	11GHz
P _{-1dB} (dBm)	14.9	13.8	N/A	15	11.7
P _{sat} (dBm)	17.9	17	9.6	18.6	16.5
PAE _{max}	20.5%	30.3%	28.5%	15.1%	12.6%
Area (mm ²)	0.25	0.115	0.11	0.175	0.22
PAE·BW/f ₀	3.32%	2.78%	3.32%	2.27%	2.31%

IV. MEASUREMENT RESULTS

The proposed mm-wave PA is fabricated in a standard digital TSMC 40 nm 1.1 V 1P7M LP CMOS technology. The chip micrograph is shown in Fig.6(a). The transformers are completely filled with dummy metal strips to comply with the strict metal density rules. The amount of the metal fills right underneath the transformer windings is kept at minimum to reduce the extra parasitic capacitance and eddy current losses. However, EM simulations reveal an additional loss of 0.2–0.4 dB for each matching network. The measured

S-parameters are shown in Fig. 6(b). With 1 V supply, the PA achieves a peak power gain of 21.6 dB at 58 GHz with BW_{-3dB} of 9.7 GHz (51.5 to 61.2 GHz). The S₁₁, S₂₂ and S₁₂ are respectively better than -6, -7 and -42 dB within 50–67 GHz. The large-signal measurements are done by a mixed-signal active load-pull setup [5]. Consuming ≤ 0.3 A from a 1 V supply, the measured P_{1dB} and P_{sat} are respectively 14.9 dBm and 17.9 dBm with 20.5% PAE_{max} at 60 GHz. The power performance is characterized in Fig. 6(d). The following parameters are maintained over 52–63 GHz: 16.9 dBm P_{sat}, 13.8 dBm P_{1dB}, and 16% PAE. Figure 7 illustrates PA's constant gain and PAE contours and also verifies the PA stability over load variation.

Table I shows a comparison of state-of-the-art 60 GHz CMOS PAs. Our PA achieves comparable BW_{-3dB} as in a 28 nm PA [4], but with a much higher PAE. For P_{sat} ≈ 18 dBm, only class-AB PA in [6] shows better PAE, but at a lower gain and BW. Furthermore, the product of PAE and BW reaches the best reported.

V. CONCLUSION

The benefits, constraints and trade-offs of different flavors of class-E/F PAs have been investigated from the mm-wave viewpoint. The resulting new proposed architecture of a fully integrated 60 GHz power amplifier was realized in 40-nm bulk CMOS. This PA utilizes a proper second-harmonic termination in the last stage and low/moderate magnetic coupling factor transformers in the intermediate stages to reach the best product of PAE and BW. The PA is also stabilized against the combination of DM and CM oscillation mode.

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